

**Notice of References Cited**

Application/Control No.

10/046,742

Applicant(s)/Patent Under  
Reexamination  
NAMBA ET AL.

Examiner

Yvette C. Thornton

Art Unit

1752

Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-6,548,220 B2	04-2003	Uetani et al.	430/270.1
	B	US-6,514,656 B1	02-2003	Nakamura et al.	430/157
	C	US-6,495,306 B2	12-2002	Uetani et al.	430/270.1
	D	US-2003/0119957 A1	06-2003	Kim et al.	524/317
	E	US-2003/0114589 A1	06-2003	Suetsugu et al.	525/132
	F	US-2003/0099900 A1	05-2003	Yamada et al.	430/270.1
	G	US-2002/0164540 A1	11-2002	Nakanishi et al.	430/270.1
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	JP 10-048826 URANO et al., abstract; POLYMER COMPOSITION AND RESIST MATERIAL CONTAINING THE SAME
	V	ET
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.